

ABSTRACT

[0057] Embodiments of a method and apparatus for determining a substrate exchange position in a processing system are provided. In one embodiment, a method of determining a substrate exchange position in a processing system includes determining an initial exchange position within a processing chamber, and resolving a change in the exchange position. The step of resolving may further include the step of sensing a change in temperature of a facet of a transfer chamber having the processing chamber coupled thereto, sensing a change in a state of the system, or sensing a change in position of the processing chamber, among others.